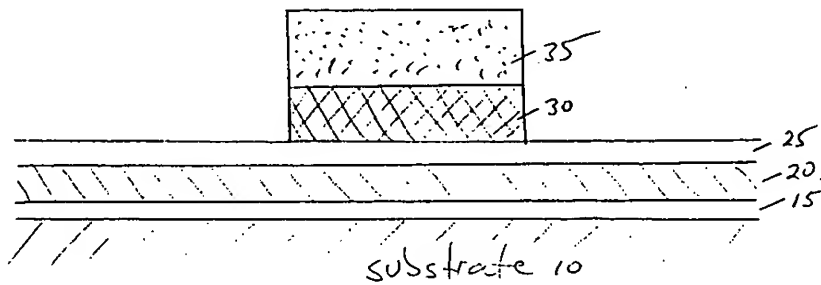
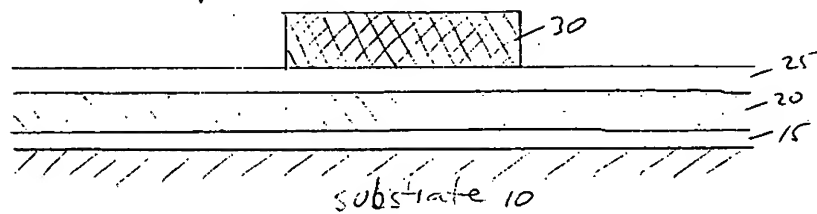


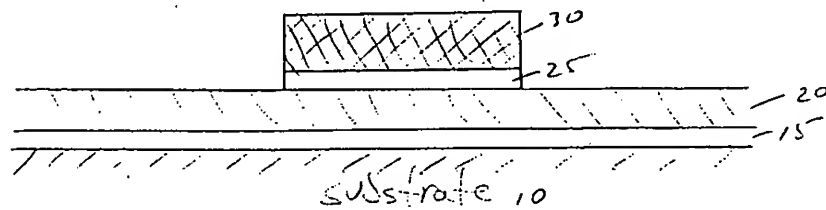
Pattern Nitride Layer



Strip off Photoresist



Etch  $WSi_x$  (stop on poly-Si)



Further etch of Poly-Si and gate oxide